

ABSTRACT OF THE DISCLOSURE

An exposure apparatus for exposing a substrate with a pattern of an original includes a projection optical system for projecting the pattern of the original onto the substrate with light from a light source, and an interferometer for measuring an optical characteristic of the projection optical system by use of the light from the light source, which passes a pinhole and the projection optical system. The pinhole has a diameter which is smaller than a diameter of an Airy disc.